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Advances in Plasma Diagnostics and Applications

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Deadline for manuscript submissions:

closed (15 January 2022)

Message from the Guest Editors

The aim of this Special Issue is to collect original research and review articles on the most recent plasma applications and to diagnose their processes, to elucidate the characteristics of plasma and mechanisms of plasma-induced processes. Potential topics include, but are not limited to:

- Experimental measurement methods and diagnostic tools for detection of radicals in gas and liquid phase
- 2. Modification in materials
- 3. Materials processing (deposition, etching, washing, etc.)
- 4. Industrial applications including water purification
- 5. Biomedical/Agricultural/Food processing applications











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Message from the Editor-in-Chief

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